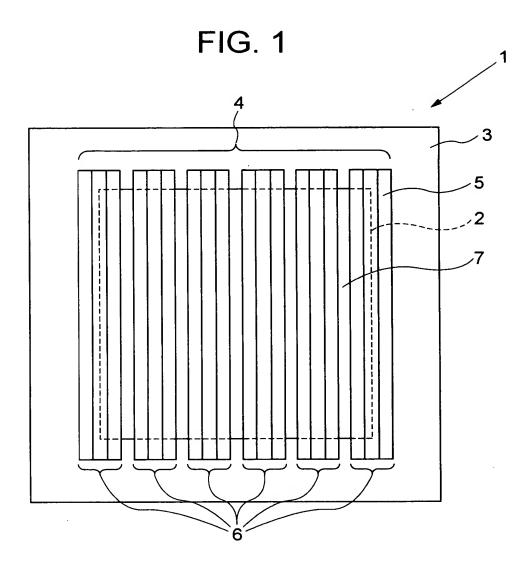
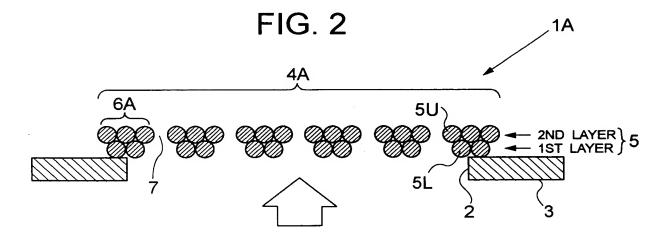
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FIG. 3

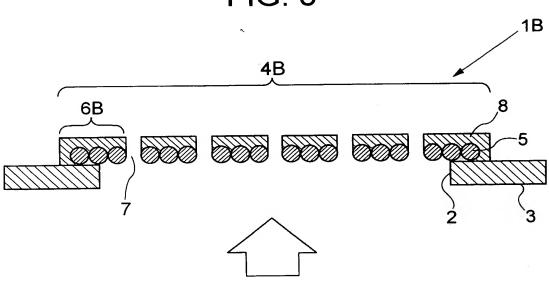


FIG. 4

4C

6C

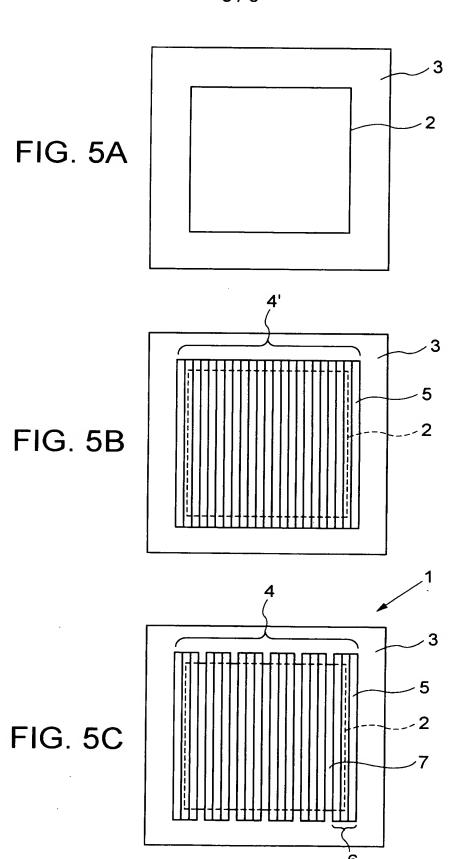
7

2

3

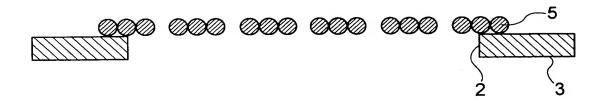
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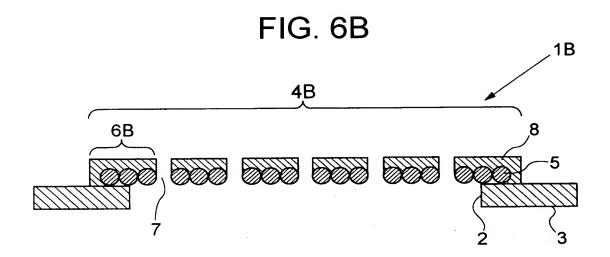
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FIG. 6A





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FIG. 7A



FIG. 7B

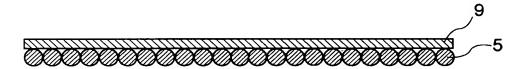


FIG. 7C

